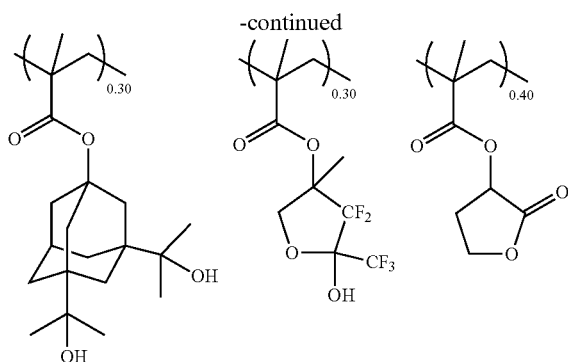
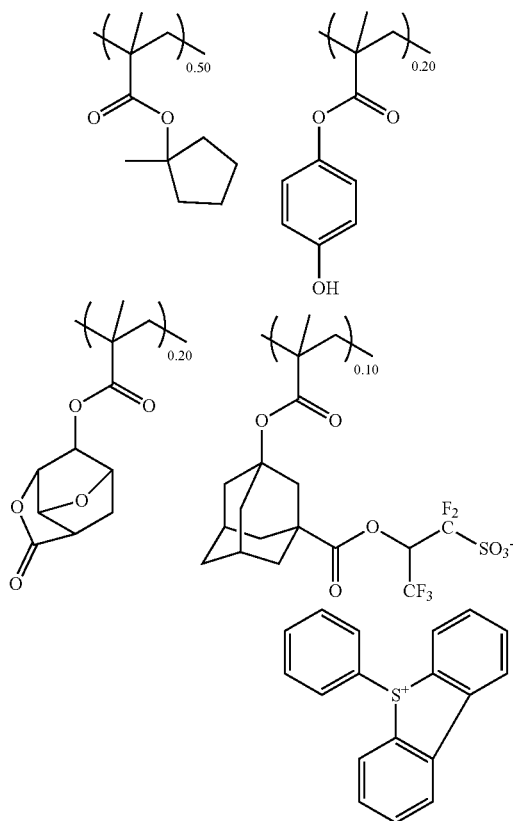


**83**

Polymer 2  
Mw = 8,100  
Mw/Mn = 1.65



Polymer 3  
Mw = 7,900  
Mw/Mn = 1.83

### Examples and Comparative Examples

Resist compositions were prepared by dissolving the polymer and selected components in a solvent in accordance with the recipe shown in Tables 1 and 2, and filtering through a filter having a pore size of 0.2  $\mu\text{m}$ . The solvent contained 100 ppm of surfactant FC-4430 (3M). The components in Tables 1 and 2 are as identified below.

#### Organic Solvents:

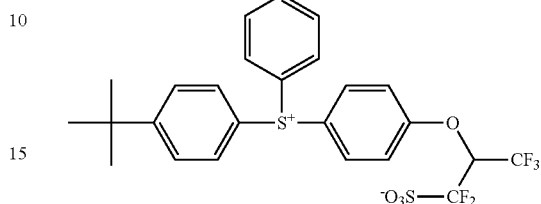
- PGMEA (propylene glycol monomethyl ether acetate)
- GBL ( $\gamma$ -butyrolactone)
- CyH (cyclohexanone)
- PGME (propylene glycol monomethyl ether)

**84**

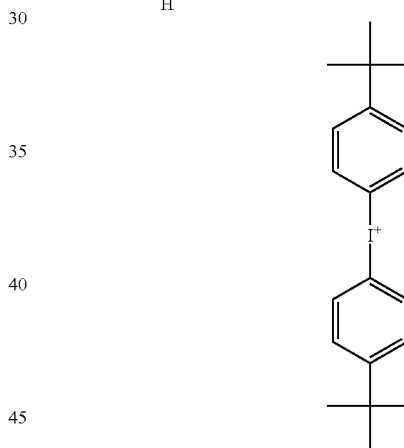
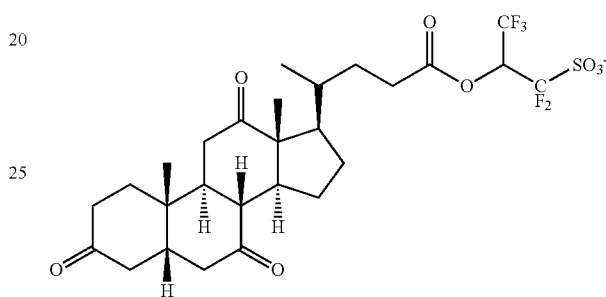
#### Acid Generators:

PAG 1 to PAG 4 of the following structural formulae

5 PAG 1



PAG 2



PAG 3

